

**AMENDMENTS TO THE CLAIMS**

**This listing of claims will replace all prior versions and listings of claims in the application:**

**LISTING OF CLAIMS:**

1. (original): A photomask formed with a light-shielding film pattern on a front surface of an optically transparent substrate, wherein:

the photomask comprises a non-device pattern composed of a light-shielding film pattern in a non-transfer area at a peripheral portion,

wherein there is provided, at a back surface of the optically transparent substrate opposed to at least a position where the non-device pattern is formed, light-transmission reducing means for reducing transmission of exposure light entering from the peripheral portion of the back surface of the optically transparent substrate.

2. (original): A photomask according to claim 1, wherein:

the light-transmission reducing means comprises a thin film or a coat having a function of reducing the transmission of the exposure light.

3. (original): A photomask according to claim 1, wherein:

the light-transmission reducing means is formed by a surface roughening treatment of the surface of the substrate.

4. (original): A photomask formed with a light-shielding film pattern on a front surface of an optically transparent substrate, wherein:

the photomask comprises a non-device pattern composed of a light-shielding film pattern in a non-transfer area at a peripheral portion,

wherein there is provided means for reducing a difference in reflectance between a pattern portion and a non-pattern portion of the non-device pattern with respect to exposure light entering from a back surface of the optically transparent substrate, thereby preventing the non-device pattern from being resolved on a transfer target surface.

5. (original): A photomask according to claim 4, wherein:

the reflectance of a light-shielding film of the pattern portion or the non-pattern portion of said non-device pattern with respect to the exposure light is adjusted so as to reduce the difference in reflectance between the pattern portion and the non-pattern portion with respect to the exposure light entering from the back surface of the optically transparent substrate.

6. (original): A photomask formed with a light-shielding film pattern on a front surface of an optically transparent substrate, wherein:

the photomask comprises a non-device pattern composed of a light-shielding film pattern in a non-transfer area at a peripheral portion,

wherein a pattern portion and a non-pattern portion of the non-device pattern are formed by a combination of light-shielding films such that the pattern portion and the non-pattern portion differ in reflectance with respect to exposure light entering from a front surface of the photomask, but no substantial difference in reflectance between the pattern portion and the non-pattern portion is generated with respect to exposure light entering from a back surface of the photomask.

7. (original): A photomask formed with a light-shielding film pattern on a front surface of an optically transparent substrate, wherein:

the photomask comprises a non-device pattern composed of a light-shielding film pattern in a non-transfer area at a peripheral portion,

wherein there is provided means for reducing a difference in reflectance between a pattern portion and a non-pattern portion of the non-device pattern with respect to exposure light entering from a front surface of the photomask, thereby preventing the non-device pattern from being resolved on a transfer target surface.

8. (original): A photomask according to claim 7, wherein:

the reflectance of a light-shielding film of the pattern portion or the non-pattern portion of the non-device pattern with respect to the exposure light is adjusted so as to reduce the difference in reflectance between the pattern portion and the non-pattern portion with respect to the exposure light entering from the front surface of the photomask.

9. (original): A photomask formed with a light-shielding film pattern on a front surface of an optically transparent substrate, wherein:

the photomask comprises a non-device pattern composed of a light-shielding film pattern in a non-transfer area at a peripheral portion,

wherein a fine pattern, which is substantially incapable of being resolved on a transfer target surface, is formed on the non-device pattern or in an area where the non-device pattern is formed.

10. (currently amended): An image device manufacturing method, comprising:

a step of performing pattern transfer by the use of the photomask according to ~~any one~~ of ~~claims 1 to 9~~claim 1.

Preliminary Amendment  
Based on PCT/JP2004/016177

11. (new): An image device manufacturing method, comprising:  
a step of performing pattern transfer by the use of the photomask according to claim 4.

12. (new): An image device manufacturing method, comprising:  
a step of performing pattern transfer by the use of the photomask according to claim 6.

13. (new): An image device manufacturing method, comprising:  
a step of performing pattern transfer by the use of the photomask according to claim 7.

14. (new): An image device manufacturing method, comprising:  
a step of performing pattern transfer by the use of the photomask according to claim 9.